

PATENTONIA 740756-1638 3/27/0/

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT application of:		)	Art Unit:	2813
Hisashi OHTANI et al.		)	Examiner:	E. Pert
Application	on No.: 08/807,737	) )	CERTIFICATE OF MAILING	
Filed:	February 27, 1997	)	deposited with the U	t this correspondence is being Inited States Postal Service with First Class Mail in an envelope
For:	or: METHOD FOR MANUFACTURING SEMICONDUCTOR DEVICE		addressed to: Commissioner for Patents, Washington, D.C. 20231, on March 19,2001  ——————————————————————————————————	

## AMENDMENT AND RESPONSE TO RESTRICTION/ELECTION OF SPECIES REQUIREMENT

Commissioner of Patents Washington, D.C. 20231

March 19, 2001

Dear Sir:

In response to the Restriction and Election of Species Requirement mailed December 19, 2000, the period for responding having been extended two (2) months, Applicants hereby elect Species III, Claims 60-62, 72-74, 81, and 83, drawn to a method of disposing a catalyst metal on a silicon dioxide "wetting layer" to improve crystallization.

03/23/2001 MRERHE

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